Attorney's Docket No.: 10559-857001/P17305

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

JUN 1 0 2005

Applicant : Sarah B. Kim et al.

Art Unit: 2814

Serial No.: 10/659,044

Examiner: Thao X Le

Filed

: September 9, 2003

Assignee: Intel Corporation

Title '

: THICK METAL LAYER INTEGRATED PROCESS FLOW TO IMPROVE

POWER DELIVERY AND MECHANICAL BUFFERING

Mail Stop AF

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

## **AMENDMENT**

In response to the Office action mailed April 11, 2005, please amend the application as follows:

Amendments to the Claims begin on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.

## CERTIFICATE OF TRANSMISSION BY PACSIMILS

I hereby certify that this correspondence is being transmitted by faculmile to the Fatent and Trademark Office on the date indicated below.

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PAGE 3/12 \* RCVD AT 6/10/2005 6:45:58 PM [Eastern Daylight Time] \* SVR:USPTO-EFXRF-1/0 \* DNIS:8729306 \* CSID:1 858 678 5099 \* DURATION (mm-ss):00-38